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## Monte Carlo Simulation of Characteristic Secondary Fluorescence in Electron Probe Microanalysis of Homogeneous Samples Using the Splitting Technique

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Abstract: Electron probe microanalysis (EPMA) is based on the comparison of characteristic intensities induced 12 by monoenergetic electrons. When the electron beam ionizes inner atomic shells and these ionizations cause the 13 emission of characteristic X-rays, secondary fluorescence can occur, originating from ionizations induced by 14 X-ray photons produced by the primary electron interactions. As detectors are unable to distinguish the origin of 15 these characteristic X-rays, Monte Carlo simulation of radiation transport becomes a determinant tool in the 16 study of this fluorescence enhancement. In this work, characteristic secondary fluorescence enhancement in 17 18 EPMA has been studied by using the splitting routines offered by PENELOPE 2008 as a variance reduction alternative. This approach is controlled by a single parameter NSPLIT, which represents the desired number of 19 X-ray photon replicas. The dependence of the uncertainties associated with secondary intensities on NSPLIT was 20 studied as a function of the accelerating voltage and the sample composition in a simple binary alloy in which this 21 22 effect becomes relevant. The achieved efficiencies for the simulated secondary intensities bear a remarkable 23 improvement when increasing the NSPLIT parameter; although in most cases an NSPLIT value of 100 is 24 sufficient, some less likely enhancements may require stronger splitting in order to increase the efficiency associated with the simulation of secondary intensities. 25

Key words: EPMA, characteristic fluorescence enhancement, Monte Carlo simulation, variance reduction 26

### INTRODUCTION 27

Electron probe microanalysis (EPMA) is a powerful analytical 28 tool, which allows chemical quantification of the elements 29 present in samples of different characteristics, along a wide 30 range of specimen compositions. When a finely collimated 31 electron beam impinges on a flat material, the characteristic 32 intensity emitted by each element composing the sample can 33 be used not only to identify these elements, but they may be 34 recorded and then compared with the corresponding inten-35 sities emitted from standards of known composition. This 36 comparison originates in the assumption that the emitted 37 characteristic intensities proportionally relate to the mass 38 concentrations of the corresponding elements, which allows 39 to eliminate geometrical and physical factors that are 40 very difficult to determine (Reed, 1993; Scott et al., 1995). 41 With adequate procedures for data reduction, the different 42 matrix effects are taken into account, usually referred to as 43 "ZAF correction" (Goldstein et al., 2003); also called "matrix 44 corrections," they were originally separated into factors 45 accounting for differences in the generation of X-rays and 46 scattering of the incident beam (Z, for atomic number

correction), absorption effects (A), and secondary fluorescence 47 enhancement (F). These matrix correction factors strongly 48 depend on the experimental conditions, mainly on the 49 incident beam energy, X-ray take-off angle, and differences 50 in composition of the standards used to compare with the 51 unknown samples. 52

When the electron beam ionizes inner atomic shells and 53 these ionizations cause the emission of characteristic X-rays, 54 secondary fluorescence can occur, originating from ioniza-55 tions induced by X-ray photons produced by the primary 56 electron interactions. This fluorescence enhancement effect 57 occurs when an atom species present in the target has an 58 inner-shell ionization energy lower than the energy of other 59 characteristic X-rays or bremsstrahlung photons that origi-60 nate within the sample. In such a case, the measured X-ray 61 intensity from the fluoresced element will include both the 62 direct electron-excited intensity as well as the additional 63 intensity generated by such enhancement. Despite 64 approaches available for the assessment of fluore 65 enhancement (Reed, 1965; Ugarte et al., 1987), it is impos-66 sible to compare these predictions with experimental data as 67 the photons produced by fluoresced atoms cannot be dis-68 criminated from the total recorded radiation. Therefore, 69 Monte Carlo simulations constitute a very important tool for 70 estimating the fluorescence enhancement and a number of 71

<sup>72</sup> specific situations have been faced with this approach
<sup>73</sup> (Fisher, 1971; Hu & Pan, 2001; Llovet & Galan, 2003;
<sup>74</sup> Fournelle et al., 2005; Fournelle, 2007).

When performing Monte Carlo simulations of radiation 75 transport, a particle track is pictured as a sequence of stochastic 76 free steps, each ending in an interaction, which changes its 77 direction of movement and its energy, and also may produce 78 secondary particles. The probabilities governing each interac-79 tion are associated with the corresponding total and differential 80 cross-sections, which allow to determine the free path between 81 successive interactions, the type of interaction taking place, and 82 the particle energy loss and angular deflection. If the number of 83 generated tracks is large enough, quantitative information on 84 the transport process may be obtained by averaging over a 85 statistically significant number of trajectories. In this work, the 86 PENELOPE routine package (Salvat et al., 2009) has been 87 chosen as it has proved to adequately describe EPMA experi-88 mental situations (Acosta et al., 1998; Llovet et al., 2003; Salvat 89 et al., 2006; Escuder et al., 2008, 2010). 90

It is important to note that, as the ionization cross-91 sections are quite small for both electrons and photons, 92 secondary fluorescence is very unlikely, because it involves 93 two ionization processes. Variance reduction techniques 94 allow to achieve better statistical uncertainties, without an 95 exaggerated increase of CPU time. In the so-called splitting 96 technique (Kahn & Harris, 1951) used here, it is assumed that 97 primary particles start moving with unit statistical weight and 98 99 each secondary particle produced by a primary one is assigned an initial weight equal to that of the primary. Splitting is also 100 offered by the PENELOPE package and consists of trans-101 forming some particles of interest into a number NSPLIT > 1 102 103 of identical particles in the same state. In order to leave the simulation results unbiased, weights are assigned to these 104 particles: each particle of interest, originally with a weight  $w_o$ , 105 is replaced by NSPLIT copies assigned with weights  $w = w_0/v_0$ 106 NSPLIT (Salvat et al., 2009). Another method for variance 107 reduction is called interaction forcing (Bielajew & Rogers, 108 1988), particularly efficient for the simulation of X-ray spectra. 109 However, for fluorescence enhancement simulation, it is not 110 as suitable as the splitting technique chosen here. The imple-111 mentation of interaction forcing in the PENELOPE package 112 favors all ionization processes for a particle kind (electrons or 113 photons), which consumes CPU time in events nonrelated 114 with the phenomenon under study, for example, L-shell 115 ionizations instead of K-shell ionizations. On the other hand, 116 splitting readily allows the specific selection of the photons 117 involved in the process of interest. 118

In this work, characteristic secondary fluorescence enhancement in EPMA has been studied by using the splitting alternative offered by PENELOPE. As the primary intensity  $I_p$ directly generated by the electron beam is enhanced by the secondary intensity  $I_s$ , corresponding to ionizations produced by other photons present in the sample, the fluorescence correction factor *F* is computed as

$$F = 1 + \frac{I_s}{I_p}.$$
 (1)

In order to analyze the dependence of the statistical uncer-

tainties of F with the NSPLIT parameter, the secondary 126 intensity I<sub>s</sub> was studied for different compositions in Fe-Ni 127 binary alloys. This combination of elements was chosen to 128 bring to evidence the fluorescence enhancement effect as both 129 Ni-K $\alpha$  and Ni-K $\beta$  photons can ionize the Fe-K shell. Three 130 typical incident energies (10, 15, and 20 keV) were selected in 131 order to perform the assessments, for each of which the 132 NSPLIT values ranged from 10 to 10,000. 133

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### MATERIALS AND METHODS

The main program PENSLAB was modified from the 135 PENELOPE 2003 distribution to take into account the 136 different characteristic enhancements; this new code is called 137 PENFLUO and was updated to fulfill the PENELOPE 2008 138 requirements. In particular, PENFLUO involves all second-139 ary fluorescence by taking advantage of the splitting variance 140 reduction technique offered by the 2008 distribution. Several 141 attempts have been made for the simulation of different 142 EPMA experiments (Llovet et al., 2005, 2014; Salvat et al., 143 2007; Bote et al., 2008), all of them taking advantage of the 144 capabilities of the geometry subroutine package PENGEOM; 145 these resultance particularly useful for the simulation of 146 particles, nater and a variety of interfaces. For 147 homogeneous flat samples, as those considered in this work, 148 the efficiencies of these programs for the assessment of the 149 fluorescence enhancements are rather low. Instead, the 150 modifications introduced to this aim in the PENSLAB pro-151 gram avoid all the CPU time that PENGEOM devotes to 152 compute distances to the quadric surfaces involved in the 153 geometry definition. 154

When an electron hits the sample a shower starts, the 155 electrons from the beam are simulated first, while second-156 generation particles are saved into a stack, then the simula-157 tion of second-generation particles begins: once the primary 158 track is completed, the program classifies the photons into 159 Ni-K $\alpha$  or Ni-K $\beta$ , and then they are cloned, by calling the 160 VSPLIT routine, that is, an integer number (NSPLIT) of 161 photons are created in the same initial conditions. When 162 Fe characteristic photons (third-generation particles) are 163 produced by these second-generation photons, they are 164 classified according to the different possibilities for second-165 ary fluorescence: Fe-K $\alpha$  by Ni-K $\alpha$ , Fe-K $\alpha$  by Ni-K $\beta$ , Fe-K $\beta$  by 166 Ni-K $\alpha$ , and Fe-K $\beta$  by Ni-K $\beta$ . In order to make PENFLUO 167 carry out this classification, the fifth component in the array 168 of particle labels ILB was used to store the information 169 corresponding to the process criginating from second- and third-generation particles (Sal 170 171 ary X-ray distribution is finally stored in counter arrays, 172 which are sent to separate output files. As mentioned in the 173 introduction, all the computed distributions are normalized 174by NSPLIT in order to not bias the results. 175

Results are then compared for different choices of 176 NSPLIT, whose values were tested between 10 and 10,000. It 177 is worth emphasizing that the splitting technique is used here 178 to reduce the statistical errors in  $I_s$ , as they bear higher 179

uncertainties than  $I_p$ ; however, splitting is not appropriate to 180 reduce the  $I_p$  uncertainties in the case of low Fe concentra-181 tion, where the fluorescence correction is most important, as 182 the number of Fe X-ray photon replicas is irrelevant 183 compared with the splitting produced in Ni photons. In 184 order to fully perform the assessment of the factor F, additional 185 simulations with no splitting (NSPLIT = 1) must be run in 186 order to achieve appropriate statistical errors. 187

The adopted values for the simulation parameters were chosen to take advantage of the CPU time for simulating electrons above the Fe inner-shell ionization energy  $(E_{abs} = 7.11 \text{ keV})$ , and photons slightly below the Fe-K $\alpha$ characteristic energy ( $E_{abs} = 6.399 \text{ keV}$ ). The choice of the remaining parameters was  $C_1 = 0.05$ ,  $C_2 = 0.05$ ,  $W_{cc} = 100 \text{ eV}$ , and  $W_{cr} = 100 \text{ eV}$ .

All the simulations for secondary fluorescence distributions were run in an Intel<sup>®</sup> Quad CPU Q8400 @ 2.66 GHz processor during 24 h in order to bring to evidence the influence of NSPLIT in the resulting statistical uncertainties for a fixed CPU time. In the case of the simulation of "primary" Fe X-rays, a higher CPU time of 96 h was required.

### **R**ESULTS AND DISCUSSION

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The predicted fluorescence enhancement bears the expected 202 behavior as a function of the concentration of the element of 203 interest. This is exemplified in Figure 1, in which the F results 204 for NSPLIT = 100 are compared with the prediction of the 205 corrected Reed's model of Venosta & Castellano (2013). As 206 shown in this reference, the original Reed's model provides 207 an 11% overestimation in the fluorescence correction factor 208 by assigning 100% K $\alpha$  yield. Therefore, the few percent dif-209 ferences between the present simulated F values and the 210 modified Reed's model are expectable in view of all the 211 approximations involved in both the original and corrected 212 algorithms. It is worth emphasizing that in the most sensitive 213



**Figure 1.** Comparison of the present Monte Carlo simulation for the fluorescence correction factor with the modified Reed's model of Venosta & Castellano (2013) for an electron beam energy of 15 keV as a function of Fe mass concentration.

case of 1% Fe, these differences would imply a correction of 214 500 ppm (0.05%). 215

All possible enhancements for 10 keV are displayed in 216 Figure 2, in which the curves obtained for different NSPLIT 217 values are shown for each enhancement situation. In order to 218 not hinder the comparisons, only error bars for NSPLIT = 219 10 and 100 are displayed. It becomes evident that the higher 220 the splitting effect, the lower the fluctuations are for each 221 curve, a behavior observed in all the simulations performed 222 along this work. It can also be seen that for enhancements 223 with low probabilities, the statistical uncertainties consequently 224 increase, as explained below. 225

It is important to notice that the F factor increases when 226 the Fe concentration decreases, but also the absolute and 227 relative uncertainties increase for lower Fe concentrations. 228 The evaluation of F involves the assessment of the secondary 229 intensities, for which the relative statistical uncertainties are 230 expected to decrease as the parameter NSPLIT increases. This 231 behavior can be analyzed by means of the efficiency of the 232 Monte Carlo algorithm (Salvat et al., 2009), which relates the 233 CPU time T for which the simulation produces an estimate f 234 for the magnitude of interest with a statistical uncertainty  $\sigma_f$ 35

$$\epsilon = \frac{1}{T} \left( \frac{\overline{f}}{\sigma_f} \right)^2$$

In the limit of large number of showers N,  $\sigma_f^2$  and T are 236 proportional to 1/N and N, respectively, and therefore  $\epsilon$  is 237 independent of N. Clearly, for fixed T (large enough), a high 238 value for  $\epsilon$  is a measure of how small the relative uncertainty 239  $(\sigma_f/f)$  is. Figure 3 shows the behavior obtained for  $\epsilon$  as a 240 function of Fe concentration, in the case of Fe-K $\alpha$  secondary 241 intensity induced by Ni-K $\alpha$  for 15 keV beam electrons, with 242 different choices of the NSPLIT parameter. As expected, 243  $\epsilon$  increases with NSPLIT, evidencing that the relative errors 244 are being reduced. It can also be seen that increasing NSPLIT 245 in one order of magnitude translates in an order of magnitude 246 gain in  $\epsilon$ , up to NSPLIT = 1,000, above which the improve-247 ment becomes smaller. 248

The trend observed for  $\epsilon$  (and therefore for the relative 249 uncertainties) can be inferred from the dependence of the 250 secondary intensities produced at fixed CPU time. As an 251 example for 20 keV beam energy, Figure 4 shows that the Fe-252  $K\alpha$  secondary intensity induced by Ni-K $\alpha$  mainly grows with 253 the Fe concentration in the range of study-similar trends 254 have been obtained for all beam energies and all enhance-255 ments. Although the Ni concentration reduces, and conse-256 quently the number of Ni fluorescing photons, a higher 257 number of Fe atoms are present in the sample; as Ni-K 258 photons are quite efficient for ionizing Fe, the result in this 259 competition is an increase in the secondary intensity. This is 260 the behavior exhibited in the plot up to certain Fe con-261 centration, from which a slight decay in the secondary 262 intensity is observed. 263

In view of the statistical nature of the uncertainties in the secondary intensities, the corresponding relative errors are expected to decrease with increasing scoring. From Figure 4, 266



Fe mass concentration (%)

**Figure 2.** Fluorescence correction factor for an electron beam energy of 10 keV as a function of Fe mass concentration: Fe-K $\alpha$  by Ni-K $\alpha$ , Fe-K $\alpha$  by Ni-K $\beta$ , Fe-K $\beta$  by Ni-K $\alpha$ , and Fe-K $\beta$  by Ni-K $\beta$ . Only error bars for NSPLIT 10 and 100 are displayed.



**Figure 3.** Efficiency of the Monte Carlo algorithm for the assessment of Fe-K $\alpha$  secondary intensity induced by Ni-K $\alpha$  as a function of Fe concentration for 15 keV incident electrons for different NSPLIT values.

267 it is clear that, as Fe concentration increases, higher sec-268 ondary events are registered, which means better variatics, 269 and consequently, smaller relative errors; this is reflected in 270 Figure 5 for the particular case of Fe-K $\beta$  intensity enhanced 271 by Ni-K $\alpha$  photons for a beam energy of 10 keV.

It is also important to note that, for the process under study, when the NSPLIT parameter increases, better statistics



**Figure 4.** Fe-K $\alpha$  secondary intensity enhanced by Ni-K $\alpha$  as a function of Fe mass concentration for beam electrons of 20 keV.

is achieved up to a certain level beyond which the extremely 274 high number of split photons prevents from attaining a 275 reasonable survey in the number of showers: the physical 276 situation of almost isotropic characteristic emission origi-277 nating in the diffusion of beam electrons would not be 278 reproduced. In addition, extremely high values of NSPLIT 279 may also lead to underflow round-off errors when the tallies 280 are incremented with vanishing contributions owing to 281 exceedingly small statistical weights. It becomes clear that 282 choosing exaggerate values for NSPLIT may distort some of 283



**Figure 5.** Relative errors for Fe-K $\beta$  intensity enhanced by Ni-K $\alpha$ at 10 keV as a function of Fe concentration for different NSPLIT values. Uncertainties for primary Fe-K $\beta$  intensity are also shown for comparison.

Iron concentration (%wt)

the produced distributions without a noticeable reduction in 284 the uncertainties. 285

It must be emphasized that the fluorescence enhance-286 ment is finally assessed by computing the F factor given by 287 equation (1). Evidently, by increasing NSPLIT, the uncer-288 tainties  $\sigma_s$  in  $I_s$  are reduced and the errors in F 289

$$\sigma_F = (F-1)\sqrt{\left(\frac{\sigma_p}{I_p}\right)^2 + \left(\frac{\sigma_s}{I_s}\right)^2},$$

are governed by the uncertainties  $\sigma_p$  in  $I_p$ . In the particular 290 enhancement shown in Figure 5, it is clear that this situation 291 occurs when choosing NSPLIT  $\geq$  100. It is therefore con-292 venient to choose an NSPLIT value high enough and per-293 form a separate (NSPLIT = 1) simulation for the primary 294 intensity with reasonable statistics. As mentioned in the 295 Materials and Methods section, in the present assessment of 296 primary Fe X-rays a CPU time of 96 h was chosen. 297

#### CONCLUSIONS 298

A Monte Carlo code was developed for the simulation of 299 the characteristic secondary fluorescence enhancement in 300 EPMA, by modifying the main program PENSLAB provided 301 in the PENELOPE 2003 distribution, and finally updated to 302 fulfill the PENELOPE 2008 requirements. This program 303 allows to assess all secondary characteristic enhancement by 304 taking advantage of the splitting variance reduction techni-305 306 que. Third-generation photons are classified through the fifth component in the array of particle labels ILB, according 307 to the process origination from this enhancement effect 308 (Salvat et al., 2009). 309

The characteristic fluorescence enhancement has been 310 simulated using several NSPLIT values for Fe-Ni alloys of 311 312 different compositions. The efficiencies for the simulated secondary intensities bear a remarkable improvement when 313 increasing the NSPLIT parameter; although in most cases an 314

NSPLIT value of 100 is sufficient, some less likely enhancements 315 may require stronger splitting in order to increase the efficiency 316 associated with the simulation of secondary intensities. 317

Although interaction forcing is a variance reduction technique, particularly efficient for reproducing X-ray spectra, for characteristic fluorescence enhancement simulation it is not as suitable as the splitting technique chosen here, as explained above. It may, however, be useful for analyzing the bremsstrahlung enhancement, as all the radiative interactions are favored and all the continuum photons with energies above 324 the binding energy of the fluoresced atoms are involved in this 325 process. This will be the subject of investigation in near future. 326

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